

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



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MARK OFFICE
Serial No.: 09/921,938
Confirmation No.: 8367

Filed: August 2, 2001

For: PHOTOLITHOGRAPHY SCHEME
USING A SILICON CONTAINING
RESIST

Assistant Commissioner for Patents
Washington, D.C. 20231

CERTIFICATE OF MAILING
37 CFR 1.8

Dear Sir:

RESPONSE TO OFFICE ACTION DATED OCTOBER 24, 2001

In response to the Office Action dated October 24, 2001, having a shortened statutory period for response set to expire on January 24, 2002, Applicants request entry and consideration of the following remarks. Although Applicant believes that no fee is due in conjunction with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4227.P1/DD/BCVD/JW for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Pending Claims:

1. A method for forming a patterned amorphous carbon layer in a multilayer stack, comprising:
 - depositing an amorphous carbon layer on a substrate;